FUJIFILM
Value from Innovation

ELECTRONIC MATERIALS

EUV NTD Resist / NTD Developer

Overview of FUJIFILM technology / product

EUV resist PCP technology

Uniform material distribution
Control de-protection reaction

PAG rich area
PDQ rich area
PAG
PDQ
PAG Connected PDQ

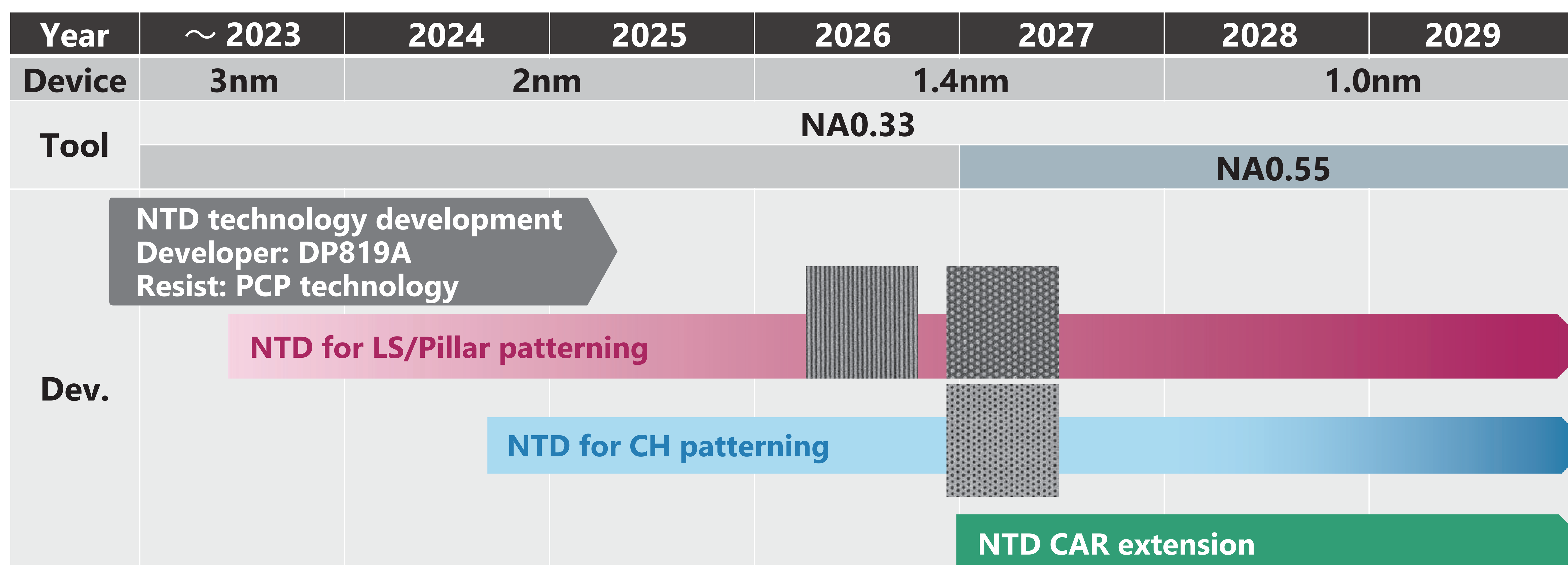
A photo-decomposable quencher connected photoacid generator (PCP) has been introduced.
By maintaining a uniform acid concentration within the resist film during EUV exposure, LWR which is a challenge of conventional chemically amplified resist (CAR) has been reduced.

NTD developer DP819A

DP001
Bridge risk
Collapse risk
DP819A
New hydrophobic developer
Suppress pattern swelling

DP819A is the unique NTD developer specifically for EUV applications. It contains a hydrophobic solvent and minimizes the swelling of the resist during development.

FUJIFILM EUV roadmap



Provide negative-tone EUV resist and EUV developer compatible with the evolved NTD process for EUV

FUJIFILM EUV CAR-NTD performance (w/ DP819A developer)